

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ando et al.
Appl. No. : 10/572,709
Filed : March 17, 2006
For : POSITIVE RESIST
COMPOSITION AND RESIST
LAMINATE FOR OW-
ACCELERATION ELECTRON
BEAM AND METHOD OF
PATTERN FORMATION
Examiner : Schilling, R.
Group Art Unit : 1795

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Neil S. Schilling, Ph.D., Reg. No. 39,901

RESPONSE TO RESTRICTION REQUIREMENT**Mail Stop Amendment**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In the Restriction/Election requirement mailed **February 19, 2008**, the Examiner restricted the pending claims into three patentably distinct inventions

- I. Claims 1-20, drawn to compositions, classified in class 430, subclass 270.1;
- II. Claims 21-39, drawn to image resist laminates, classified in class 430, subclass 14; and
- III. Claims 40-43, drawn to electron beam exposure, classified in class 430, subclass 296.

In response to the Restriction Requirement, Applicants hereby elect **Group I** (Claims 1-20), without traverse. Thus, claims 1-20 encompass the elected invention. Applicants reserve the right to pursue the remaining invention(s) in a divisional application(s).

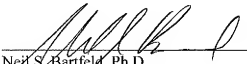
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No fees are believed to be due. However, please charge any additional fees, including any fees for additional extension of time, or credit overpayment to Deposit Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 3/5/08

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